



Patent
Attorney Docket No. 015290-502

In re Patent Application of

Helen H. ZHU et al.

Application No.: 09/820,694

Filing Date: March 30, 2001

Title: METHOD OF PLASMA ETCHING SILICON NITRIDE

Group Art Unit: 2823

Examiner: J. J. Maldonado

Confirmation No.: 7374

PETITION FOR EXTENSION OF TIME

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The following extension of time is requested to: extend the time for responding to the Final Official Action dated November 20, 2003

one month to March 20, 2004 ☐ \$55.00 (2251) ☒ \$110.00 (1251)

- ☐ The shortened statutory period has been reset by an Advisory Action dated _____.
- ☒ An extension fee in the amount of \$ 110.00 is enclosed.
- ☐ Charge \$ _____ to Deposit Account No. 02-4800.


The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. §§1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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Date: March 19, 2004

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